





Synthesis and Characterization of Atomic and Electronic Properties of Graphene Directly Grown on Dielectric Substrates

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Research Issues in ARON Lab

Nano Electronics



- CVD Graphene/H-Ge(110) & Graphitic Carbon Nitride
- TMD (WSe2 & ReS2) & TMC
- In-house DFT Calculations



Nano Optics



- Photofluidics of AuNP Corral
- Graphene Plasmonics w/ AuNP
- EL Study of QD for Display
- Perovskite for Solar Cell
- In-house Simulations







Graphene-based Heterostructures



- Direct CVD Growth of Graphene/h-BN and BGB
- Direct CVD Growth of Graphene on Dielectric Substrates
- Reciprocal CVD Growth of Polycrystalline Bilayer Graphene





Qingshan YANG



Facilities in ARON Lab





IKI

In house DFT Calculations



1.5 V



- Tools: VASP or Quantum Espresso
- GGA within PBE formalism was employed for the exchange– correlation potential.
- PAW method and a plane-wave basis set with an energy cutoff of 500 eV
- Van der Waals Correction
- Spin-polarized DOS
- Band Calculation by HSE Exchange Correction
- STM Image Simulation
- 1 node of 20 cpu's in CINAP(IBS)@SKKU
- Tachyon 2 @KISTI

2.0 V

In house FDTD Simulation









Graphene Grown on/with h-BN



Issue 1: Graphene/h-BN Heterostructure



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A Platform for Large-Scale Graphene Electronics – CVD Growth of Single-Layer Graphene on CVD-Grown Hexagonal Boron Nitride

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Catalytic Transparency of Hexagonal Boron Nitride on Copper for Chemical Vapor Deposition Growth of Large-Area and High-Quality Graphene

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Motivation





- Most of graphene measurements were done on this way.
- Roughness (1) and charge impurities (2) of SiO_2 with chemical impurities (3) underneath of graphene disturbs the graphene properties.

Transferring h-BN and Graphene sequentially on SiO₂



- h-BN layers are used as a flat surface without charge impurities.
- Chemical impurities by transferring graphene or h-BN with wet chemistry still remains as scatter.

Motivation

- Transferring Graphene/h-BN on SiO₂



- Approach: Transfer the clean interface by using a hybrid structure.
 - I. Large Area CVD Growth of h-BN on Cu foil
 - II. Sequential CVD Growth of Graphene on h-BN/Cu
 - III. Etching Cu foil
 - IV. Transfer this Graphene/h-BN structure with keeping the clean interface.

Crystallinity (TEM & SAED)



Robust enough to keep the layered structure

Two distinct Single crystal phases from both of graphene and h-BN at least 200 nm x 200 nm



Graphene Quality (Raman Spectroscopy)





Electrical Properties



- a) Resistance versus applied gate voltage for CVD-grown graphene/h-BN, mechanically transferred graphene/h-BN, and graphene on SiO₂.
- b) Carrier mobility as a function of charge carrier density for the three devices.
- c) Temperature dependences of the resistivity at $V_g V_{Dirac} = 10$ V for the three devices.



Atomic and Electronic Structures (STM/STS)





Growth Mechanism (DFT Calculations)



Growth Mechanism (Surface Potential)

AFM Topography



Raman Peak (h-BN) Mapping



KPFM Mapping





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Issue 2: BN/Graphene/BN Heterostructure (BGB)



Nanoscale

COMMUNICATION



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DOI: 10.1039/c5nr00889a www.rsc.org/nanoscale *In situ* synthesis of a large area boron nitride/ graphene monolayer/boron nitride film by chemical vapor deposition[†]

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Growth Dynamics





Growth Dynamics

BN Growth on Graphene/h-BN/Copper



BN Growth on Graphene/Copper





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Crystal Structure (TEM/SAED)

Graphene/h-BN



BN(40 min)/Graphene/h-BN



BN(60 min)/Graphene/h-BN





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Device Performance





Issue 2 : Double Layer Graphene Film



Growth Dynamics : A Role of h-BN



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Statistical Study (Optical Microscopy)



Intra-Island Angles

Inter-Island Angles



⊿ab



Quality and Epitaxy of Multilayer Graphene



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Quality and Epitaxy of Bilayer Graphene



Figure 1. (a) An optical reflection image of CVD graphene transferred to Si/285 nm SiO₂ and a large area widefield G band Raman image of the same region. The G band image contains striking features in the multilayer regions, which are not seen in the reflection image. (inset) Structure of tBLG with a twist angle θ. (b) Dark field TEM, G band, and 2D band Raman images of the same multilayer tBLG sample. The features in the Raman image correspond well with twisted bilayer domains identified with DF-TEM (θ is labeled for each domain in the TEM image]. Raman spectra for several domains are also shown.



Quality and Epitaxy of Bilayer Graphene



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THANK YOU